



Attorney Docket No.: 042390.P7832

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Li-Shun Wang, John Chu

Serial No.: 09/476,633

Filed: December 31, 1999

For: REMOVAL OF RESIDUE FROM A  
SUBSTRATE

Art Unit: 2823

Examiner: Garcia, J.

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AMENDMENT AND RESPONSE TO FINAL OFFICE ACTION

Box AF  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In connection with the Final Office Action mailed on February 6, 2001 regarding the above-referenced Application, the Applicants respectfully request consideration of the following amendments and remarks.

Presented below are amended claims in a clean-unmarked format.

IN THE CLAIMS

- 1 1. (Three Times Amended) A method of removing a particle from a [metal]
- 2 surface of a metal plug formed in a via comprising:
- 3 introducing a first agent to a metal layer;
- 4 polishing the metal layer with the first agent; [and]
- 5 after polishing the metal layer, introducing a second agent comprising hydrogen
- 6 peroxide to [a] rinse the surface of the metal plug; and
- 7 removing at least one particle from the surface of the metal plug.

Please,  
Do not  
enter.  
SKG  
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